

[54] CONTINUOUS AMORPHOUS SOLAR CELL PRODUCTION SYSTEM

[75] Inventors: Masatsugu Izu, Birmingham; Vincent D. Cannella, Detroit; Stanford R. Ovshinsky, Bloomfield Hills, all of Mich.

[73] Assignee: Sovonics Solar Systems, Solon, Ohio

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[58] Field of Search 118/718, 719, 725, 50.1, 118/720, 721; 427/38, 39, 85, 86

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Primary Examiner—John H. Newsome

Attorney, Agent, or Firm—Marvin S. Siskind

[57] ABSTRACT

The continuous production of solar cells by the glow discharge (plasma) deposition of layers of varying electrical characteristics is achieved by advancing a substrate through a succession of deposition chambers. Each of the chambers is dedicated to a specific material type deposition. The chambers are mutually isolated to avoid the undesired admixture of reaction gases therebetween. Each plasma deposition is carried out in its glow discharge area, chamber, or chambers, with isolation between the plasma regions dedicated to different material types. Masking, mechanical or lithographic, can be employed relative to the substrate to cause the deposition in the desired configuration. After the semiconductor deposition is complete, top contact and anti-reflection layer or layers are deposited, followed by a protective lamination.

8 Claims, 7 Drawing Figures

